



## XPSpro Coating System

The XPSpro is an ALD system especially designed for high throughput in thin film coating applications.

Unique reaction chamber design guarantees customer orientated, highly repeatable and accurate film deposition on planar and freeform substrates.

A compact footprint and modular design makes the XPSpro the optimal tool for broad spectrum of customer's projects.

### Key features

- Variable load volume
- Excellent uniformity and spectral accuracy even on freeform objects
- Very low scattering and absorption losses
- Almost bulk-like layer microstructure
- Excellent humidity and aging resistance
- High LIDT stability
- Internal stress is lower than in MS and IBS



### Technical specifications

Basic capacity:	Option A*: up to $\varnothing 300$ mm or $\sim 100$ pcs. of $\varnothing 25.4$ mm
	Option B*: up to 1000 mm in one dimension
Substrate treatment:	150 - 300 °C
Available materials:	SiO <sub>2</sub> / Al <sub>2</sub> O <sub>3</sub> / Ta <sub>2</sub> O <sub>5</sub> / HfO <sub>2</sub>
Spectral range:	UV - NIR
Thickness uniformity:	< 0.5 % for Al <sub>2</sub> O <sub>3</sub>
Typical cycle time:	< 2 s
Material lines, up to:	4 gas lines
	4 liquid sources
	4 hot sources (to 300 °C)
Compatibility:	Clean Room Class 100
Dimensions, (L x W x H)	1500 x 600 x 1850 mm



*\*In order to meet your requirements each option can be rearranged*